

(b) Amendment to the Claims

Please cancel claims 12 and 13 and add new claims 26 and 27 as follows.

The status of all the claims is listed below.

1. - 25. (Cancelled)

26. (New) A plasma treatment apparatus for individually treating a plurality of reactors having different impedances comprising:

a plurality of different movable reactors each having an evacuable interior where at least one treatment substrate is set, each movable reactor having an impedance different from another of the plurality of different movable reactors and each movable reactor configured to perform a different plasma treatment from another of the plurality of different movable reactors;

high-frequency power supply means for supplying high-frequency power into a selected movable reactor from the plurality of different movable reactors to cause glow discharge to take place in the selected movable reactor, the high-frequency power supply means having a connecting portion for connecting with the selected movable reactor;

a plurality of impedance matching circuits respectively corresponding to the plurality of different movable reactors, the plurality of impedance matching circuits respectively configured to cause different impedances of the

corresponding plurality of different movable reactors to match an impedance of the high-frequency power supply means; and

moving means for moving the selected movable reactor into a plasma-treatment position in which the selected movable reactor is connected to the high-frequency power supply means via a corresponding impedance matching circuit,

wherein the high-frequency power supply means is configured to individually and detachably connect to a movable reactor which is selected from the plurality of different movable reactors via a corresponding impedance matching circuit of the plurality of impedance circuits, and

wherein each of the plurality of impedance matching circuits is detachably connectable to the high-frequency power supply means.

26. (New) The plasma treatment apparatus of claim 25, wherein the substrate is for an electrophotographic photosensitive member.